Supporting Information

Writing Highly Ordered Macroscopic Patterns in Cylindrical Block Polymer Thin Films via Raster Solvent Vapor Annealing and Soft Shear

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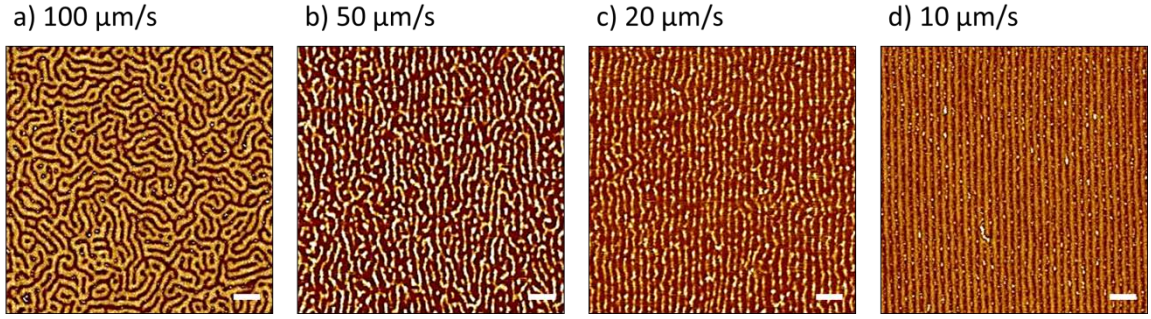

Figure S1. Atomic force microscopy (AFM) phase images of the poly(styrene-*b*-isoprene-*b*-styrene) [SIS] thin films processed at different rastering speeds (a) 100 µm/s; (b) 50 µm/s; (c) 20 µm/s; (d) 10 µm/s. Scale bars represent 200 nm.

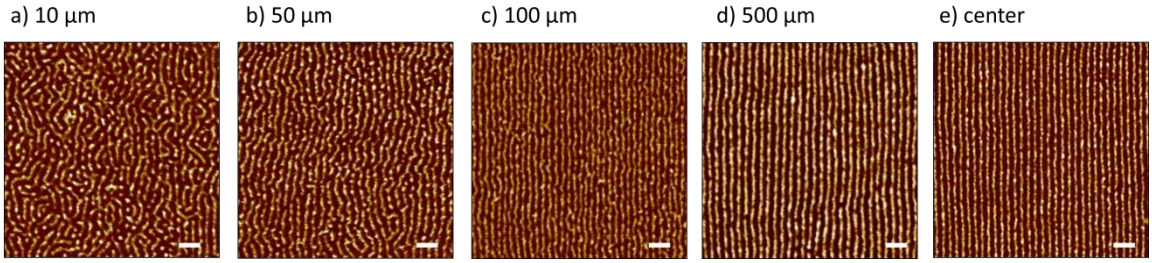

Figure S2. AFM phase images of the SIS thin films near the edge of the rastered region *vs.* center of the rastered area. The total rastered area was 4000 µm (4 mm) wide. Distances from the edges are noted above the corresponding AFM phase images. Note: Approximately 95% of the rastered area shows high-quality cylinder alignment. Scale bars represent 200 nm.